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COMING EVENTS

2005

- Microscopy and Microanalysis 2005 July 31- August 4, 2005, Honolulu, HA www.msa.microscopy.com
- ✓ 12th Canadian Semiconductor Technology Conference August 16 -19, 2005, Ottawa, Ontario, Canada http://www.canadiansemiconductor.org
- Advanced Course on Light Microscopy September 5-9, 2005, Santa Barbara, CA www.lifesci.ucsb.edu/mcdb/events/imaging_workshop/index.html
- ✓ IACEM 2005--8th Inter American Cong. of Electron Microsc. September 25-30, 2005, Havana, Cuba www.ciasem2005.cigb.edu.cu
- Scanning Probe Microscopy in Life Sciences October 13, 2005, Berlin, Germany www.spm-workshop.jpk.com
- ✓ Society for Neuroscience November 12-16, 2005, Washington, DC info@sfn.org
- Materials Research Society esp: In-Situ Electron Microscopy of Materials, Symposium MM November 28- December 2, 2005, Boston, MA info@mrs.org
- ✓ 9th International Symposium on Biomineralization December 6-9, 2005. Pucón, Chile www.cimat.cl/biomin09
- American Society for Cell Biology December 10-14, 2005, San Francisco, CA www.ascb.org

2006

✓ PITTCON 2006

March 12-17, 2006, Orlando, Florida www.pittcon.org

- ✓ American Soc. for Biochemistry and Molecular Biology April 1-5, 2006, San Francisco, CA www.asbmb.org
- SCANNING 2006
 April 25-27, 2006, Washington, DC
 www.scanning-fams.org
- Microscopy and Microanalysis 2006 August 6-10, 2006, Chicago, IL www.msa.microscopy.com
- ICEM XVI International Microscopy Congress September 3-8, 2006, Sapporo, Japan www.imc16.jp
- American Society for Cell Biology December 9-13, 2006, San Diego, CA www.ascb.org

2007

 Microscopy and Microanalysis 2007 August 5-9, 2007, Fort Laurderdale, FL www.msa.microscopy.com

2008

Microscopy and Microanalysis 2008

August 3-7, 2008, Albuquerque, NM www.msa.microscopy.com

Please check the "Calendar of Meetings and Courses" in the MSA journal "Microscopy and Microanalysis" for more details and a much larger listing of meetings and courses.

The objective of this publication is to provide material of interest and value to working microscopists!

The publication is owned by the Microscopy Society of America (MSA) and is produced six times each year in odd months, alternating with MSA's peer-reviewed, scientific journal *Microscopy and Microanalysis*. We greatly appreciate article and material contributions from our readers—"users" as well as manufacturers/suppliers. The only criterion is that the subject matter be of interest to a reasonable number of working microscopists. *Microscopy Today* has authors from many disparate fields in both biological and materials sciences, each field with it's own standards. Therefore *MT* does not have a rigid set of style instructions and encourages authors to use their own style, asking only that the writing be clear, informative, and accurate. Length: typical article length is 1,500 to 2,000 words plus images, longer articles will be considered. Short notes are encouraged for our Microscopy 101 section.

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